

Amendments to the Specification:

The paragraph starting at page 1, line 20, is amended and now reads as follows:

-- United States Patent ~~6,822,729~~ 6,930,758 is incorporated herein by reference and discloses a method for microlithographic image generation wherein microlithography with tangentially polarized illumination is explained in detail as is the preparation thereof. However, no suggestion is provided in this publication as to a connection to refraction characteristics of the lens material. Systems having radial polarization are also discussed in this publication. --

The paragraph starting at page 3, line 14, is amended and now reads as follows:

-- United States Patent ~~6,822,729~~ 6,930,758 discloses that the tangential or radial polarization, which is needed as a condition precedent for the use of double-refracting material, has advantages also for image contrast and can be made available in different ways. According to the invention, it is therefore provided that all lenses, which consist of optically single-axis double-refracting material, are aligned with the optical crystal axis parallel to the optical axis. --